

an insulating film provided at least on the electrode wires so as to have openings in predetermined areas at least either on the scanning electrode wiring or on the signal electrode wiring; and

a metal layer stacked on the electrode wiring in the openings.

7. (amended) A display device, comprising:

an active matrix substrate; and

an electro-optical medium driven by the active matrix substrate, the active matrix substrate including: electrode wires constituted by scanning electrode wiring and signal electrode wiring that are arranged in a lattice; an insulating film provided at least on the electrode wires so as to have openings in predetermined areas at least either on the scanning electrode wiring or on the signal electrode wiring; and a metal layer stacked on the electrode wiring in the openings.

10 (amended) The display device as defined in claim 7, wherein

at least either the scanning electrode wiring or the signal electrode wiring are fabricated from a transparent conducting oxide film.

14. (amended) an image-capturing device, comprising:

an active matrix substrate; and

a photoconductor of which electric charge is read by the active matrix substrate

the active matrix substrate including: electrode wires constituted by scanning electrode wiring and signal electrode wiring that are arranged in a lattice; an insulating film provided at least on the electrode wires so as to have openings in predetermined areas at least either on the scanning electrode wiring or on the signal electrode wiring; and a metal layer stacked on the electrode wiring in the openings.

17 (amended) The image-capturing device as defined in claim 14, wherein

at least either the scanning electrode wiring or the signal electrode wiring are fabricated from a transparent conducting oxide film.

22. (amended) A method of manufacturing an active matrix substrate, comprising the steps of:

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- (a) forming scanning electrode wiring and signal electrode wiring, for acting as electrode wires, arranged in a lattice on a substrate;
 - (b) forming an insulating film at least on the electrode wires so as to have openings in predetermined areas at least either on the scanning electrode wiring or on the signal electrode wiring; and
 - (c) forming a metal layer selectively in the openings on the electrode wiring.

Kindly add new claims 27-30, as follows:

27. (new) The method of manufacturing an active matrix substrate as defined in claim 22, wherein:

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the opening and the metal layer are provided along the length of at least either one of the scanning electrode wiring and the signal electrode wiring.

28. (new) The active matrix substrate as defined in claim 1, wherein the opening and the metal layer are provided along the length of at least either one of the scanning electrode wiring and the signal electrode wiring.

29. (new) The display device as defined in claim 7, wherein the opening and the metal layer are provided along the length of at least either one of the scanning electrode wiring and the signal electrode wiring.

30. (new) The image-capturing device as defined in claim 14, wherein the opening and the metal layer are provided along the length of at least either one of the scanning electrode wiring and the signal electrode wiring.